

ABSTRACT

Included are: (a) supplying a first processing gas containing a first element and a halogen to a substrate; (b) supplying a second processing gas including a N-N bond and a N-H bond to the substrate; and (c) performing (a) and (b) X times, X being a natural number, in a state where the substrate is heated to a temperature of 250 degrees C or lower to form a first film containing the first element.

Fig. 4